



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Smith, et al.

Docket No: TI-25250

Serial No: 09/199,829

Examiner: K. Eaton

Conf. No: 4119

Art Unit: 2823

Filed: 11/25/98

For: HYDROGEN PLASMA PHOTORESIST STRIP AND POLYMERIC RESIDUE
CLEANUP PROCESS FOR OXYGEN-SENSITIVE MATERIALS

13/Response
Chusa
7-23-01

RECEIVED
JUL 19 2001
TECHNOLOGY CENTER 2800

AMENDMENT UNDER 37 C.F.R. § 1.111

Assistant Commissioner For Patents
Washington, DC 20231

MAILING CERTIFICATE UNDER 37 C.F.R. §1.8(a)

I hereby certify that the above correspondence is being deposited with the U.S. Postal Service with sufficient postage as First Class Mail in an envelope addressed to: Assistant Commissioner for Patents, Washington, DC 20231 on 7-13-01.

Ann Trent
Ann Trent

Dear Sir:

Responsive to the Office Action mailed April 11, 2001, in connection with the above identified application, Applicant respectfully submits the following remarks.